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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
09/955,288	09/19/2001	Joo-Hyong Lee	LGS/S-0030A	LGS/S-0030A 9373	
34610	7590 03/07/2003				
FLESHNER & KIM, LLP			EXAMINER		
	N PARKWAY, SUITE Y, VA 20151	125	DIAZ, JOSE R		
			ART UNIT	PAPER NUMBER	
			2815		
DATE MAILED: 03/07/		DATE MAILED: 03/07/2003	;		

Please find below and/or attached an Office communication concerning this application or proceeding.

—			9h
,	Application No.	Applicant(s)	
. Advisory Action	09/955,288	LEE, JOO-HYONG	
,	Examiner	Art Unit	
	José R Díaz	2815	
The MAILING DATE of this communication appe	ears on the cover sheet with the c	orrespondence add	ress
THE REPLY FILED 20 February 2003 FAILS TO PLACE Therefore, further action by the applicant is required to a final rejection under 37 CFR 1.113 may only be either: (1) condition for allowance; (2) a timely filed Notice of Appea Examination (RCE) in compliance with 37 CFR 1.114.	oid abandonment of this applicate) a timely filed amendment which	ition. A proper reply n places the applica	y to a tion in
PERIOD FOR RE	EPLY [check either a) or b)]		
a) The period for reply expiresmonths from the mailin			
b) The period for reply expires on: (1) the mailing date of this A no event, however, will the statutory period for reply expire I ONLY CHECK THIS BOX WHEN THE FIRST REPLY WAS 706.07(f).	ater than SIX MONTHS from the mailing	g date of the final rejection	on.
Extensions of time may be obtained under 37 CFR 1.136(a). The fee have been filed is the date for purposes of determining the period of fee under 37 CFR 1.17(a) is calculated from: (1) the expiration date of (2) as set forth in (b) above, if checked. Any reply received by the Officially filed, may reduce any earned patent term adjustment. See 37 C	of extension and the corresponding amo the shortened statutory period for reply ce later than three months after the mail	unt of the fee. The appr originally set in the final	opriate extension Office action; or
1. A Notice of Appeal was filed on Appellant's 37 CFR 1.192(a), or any extension thereof (37 CFF	s Brief must be filed within the pe R 1.191(d)), to avoid dismissal of	eriod set forth in fithe appeal.	
2. The proposed amendment(s) will not be entered be	ecause:		
(a) they raise new issues that would require further	er consideration and/or search (s	see NOTE below);	
(b) they raise the issue of new matter (see Note b			
(c) they are not deemed to place the application in issues for appeal; and/or	n better form for appeal by mate	rially reducing or sir	mplifying the
(d) they present additional claims without canceli NOTE:	ng a corresponding number of fi	nally rejected claim	S.
3. Applicant's reply has overcome the following rejecti	on(s):		
4. Newly proposed or amended claim(s) would canceling the non-allowable claim(s).	be allowable if submitted in a se	eparate, timely filed	amendment
5. ☑ The a) ☐ affidavit, b) ☐ exhibit, or c) ☑ request for application in condition for allowance because: Se		dered but does NO	T place the
6. The affidavit or exhibit will NOT be considered bec raised by the Examiner in the final rejection.	ause it is not directed SOLELY to	o issues which were	e newly
7. For purposes of Appeal, the proposed amendment explanation of how the new or amended claims we			and an
The status of the claim(s) is (or will be) as follows:			
Claim(s) allowed:			
Claim(s) objected to:			
Claim(s) rejected: <u>1-5 and 11-25</u> .		\sim	
Claim(s) withdrawn from consideration:			
8. The proposed drawing correction filed on is	a) approved or b) disapp	roved by the Exami	ner.
9. Note the attached Information Disclosure Statemen	nt(s)(PTO-1449)	A-1	
10. Other:	$(\Lambda \Lambda$	<i>y</i> .	
		EDDIE LEE	
	SUPERVISOR	RY PATENT EXAMINE	R

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Continuation Sheet (PTO-303)

Continuation of 5. does NOT place the application in condition for allowance because: the references anticipate the claimed invention. Applicant argues that the references Farrenkopf and Zunino fail to teach an interface between a well and a substrate, and that the reference Wong fails to teach a buried layer/heavily doped region, which is separated from the contact region. However, the Examiner disagrees in view of the following remarks.

With regards to the interface between a well and a substrate, it seems that Applicant has overlooked the inconsistency of the claimed invention. In fact, it seems that Applicant use the term "substrate" interchangeably in the claims referring to either a whole substrate that include the wells or a portion of the substrate that does not include the wells. For instance, in claim 1, lines 3-4 Applicant use the term "substrate" referring to a whole substrate that include the first well. Then, in lines 8-9 of claim 1, Applicant changes the meaning of the term "substrate" to refer to a portion of the substrate that has a common boundary with the first well. Therefore, since Applicant fails to clearly define the term "substrate" in the claims, one of ordinary skill in the art cannot identify where in the device "an interface" is formed. As such, the rejections over Farrenkopf and Zunino are considered to be proper since the location of the interface is undetermined

With regards to the limitation that the heavily doped region is separated from the contact region, Applicant should note that nowhere in the claims such a limitation is included. For instance, claims 1 and 24 recite the limitation of a heavily doped region formed between a contact region and a well/substrate interface, and claim 15 recites the limitation of a heavily doped region not formed between first/second wells interface. Nowhere in such claims, Applicant specifically states that the heavily doped region is separated from the contact region, as now argued.

With regards to the arguments that the doped region of Wong is not a buried region, Applicant is advised that during patent examination, the pending claims must be "given the broadest reasonable interpretation consistent with the specification" (see MPEP 2111). In view of that, Applicant teaches that the "buried layer" (105, 106) is in fact a doped region, which is formed at a predetermined location beneath the major surface of the substrate (51) (see Figure 2 and page 10, lines 11-14 of the Specification). Wong teaches the same structural requirement in Figure 2G, wherein Wong clearly shows a doped region (16, 22) formed at a predetermined location beneath the major surface of the substrate (4), as required by Applicant. Therefore, broadly speaking Wong anticipates the claimed limitation.